



Figure 1. Current-voltage characteristics of Au-Ti-ZrO₂:Al₂O₃-TiN structures. The ZrO₂:Al₂O₃ films with Al:Zr atomic ratios of 0.044-0.050 (upper panel) and 0.28-0.35 (lower panel) were deposited using ZrO₂:Al₂O₃ cycle ratios of 24:1 and 4:1, respectively.